III.D FOURIER IMAGE PROCESSING TECHNIQUES

III.D.1 Optical Diffraction

OD the simplest and classically the most widely practiced Fourier image processing technique

- Initial step in many image processing studies

Main advantage:

Objective way to assess and reveal periodic structural information

Klug and Berger (1964) were 1st to use an optical bench to examine diffraction patterns of electron micrographs and analyze biological structure in images of stained specimens

III.D.1 Optical Diffraction III.D.1.a Forming the Diffraction Pattern



Adapted from Slayter, Fig. 19-12a, p.448

III.D.1 Optical Diffraction III.D.1.b Experimental Apparatus Simple (Linear) Optical Diffractometer



- A. Laser
- B. Shutter
- C. Beam expanding lens
- D. Pinhole
- E. Adjustable diaphragm
- F3. Diffraction lens
- G. Micrograph
- H. Viewing screen or camera



- S_o Radiation source
- L_0 Beam expanding lens
- $\tilde{S_1}$ Pinhole
- L₁ Collimating lens
- A Micrograph
- L₂ Diffraction lens
- M Mirror
- F Diffraction pattern focal plane

III.D.1.b Experimental Apparatus

The UCLA Folded Optical Diffractometer (Circa 1972)



FOLDED OPTICAL DIFFRACTOMETER

- 1 power supply
- 2 4.5mW He-Ne laser
- 3 polarizing filter
- 4 spatial filter & beam expander

- 5 EM plate holder
- 6 limiting aperture
- 7 camera or filter mask position
- 8 35mm camera body

III.D.1 Optical Diffraction III.D.1.c Applications

- Accurate measurement of lattice parameters (unit cell dimensions)
- Detect rotational and translational symmetry elements
- Detect and measure specimen **preservation** (distortions, overall resolution, radiation damage) for selecting best images for further image analysis
- Assess short and long range order in periodic specimens
- Identify signal and noise in images
- Determine **electron optical conditions**, i.e. contrast transfer function (focus, drift, astigmatism, etc.) at time micrograph was recorded
- Superb **teaching device** (principles of diffraction, symmetry and Fourier transforms)

III.D.1 Optical Diffraction III.D.1.c Applications

A few more...

- Able to examine **small regions** of specimen
- Determine **relative orientation** of multilayered specimens (*e.g.* stacked 2D sheets or opposite sides of two-sided structures)
- Determine the **hand** of 3D structures (from metal-shadowed or tilted specimens)

Optical Diffraction of Negatively Stained Catalase Crystal



From Baker thesis, Fig. B-5, p.109

Effect of Lattice Disorder on Diffraction Pattern



Ordered lattice

2-D disorder of ±10%



Vertical disorder of ±10%





From Misell, Fig. 3.17, p.72

Focus Series of Thin Carbon Film with Gold Atoms



From Misell, Fig. 3.8, p.60

BIO 595R

I.C.3 Phase Contrast Transfer Function



Plot of phase contrast as a function of structure size. (a) Objective lens in focus.(b) Objective lens 78 nm underfocus. (c) Objective lens 234 nm underfocus

(Agar, p. 282)

BIO 595R I.C.3 Phase Contrast Transfer Function

Dependence of CTF on **resolution**, **wavelength**, **defocus** and **spherical aberration** is given by:

$$CTF(v) = -\left\{ \left(1 - F_{amp}^{2}\right)^{\frac{1}{2}} \bullet \sin(\chi(v)) + F_{amp} \bullet \cos(\chi(v)) \right\}$$

where

$$\chi(\nu) = \pi \lambda \nu^2 \left(\Delta f - 0.5 C_s \lambda^2 \nu^2 \right)$$

v = spatial frequency (in Å⁻¹)

 F_{amp} = fraction of amplitude contrast

- λ = electron wavelength (in Å), where $\lambda = 12.3/\sqrt{V + 0.000000978 \cdot V^2}$ (= 0.037, 0.025, and 0.020Å for 100, 200, and 300 keV electrons, respectively)
- V = voltage (in volts)
- Δf = underfocus (in Å)
- C_s = spherical aberration of objective lens of microscope (in Å)

Axial Astigmatism in Images of Thin Carbon Film



III.D.1 Optical Diffraction Defects in Images of Thin Carbon Film



Miscentered objective aperture



From Steven et al., (1976) Fig. 1, p.192

End of Sec.III.D.1